

EAST: [1055004 litho mask.wsp:1]

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12 with 45

	U	Inventor	Document	Issued	P	Title	Current	Current	Retrieval	S	C	P	Image	No	P
1		Ota, Kazuya	US 5477309	1995	13	Alignment apparatus	355/67	355/68		P	P	P		US 547730	
2		Mitaka, S	US 200200	2002	18	Photomask and manufacturing metho	430/5	430/270.1		P	P	P		US 20020	
3		Okamoto, Y	US 200200	2002	41	Method of manufacturing photomask	438/37	257/E21.57		P	P	P		US 20020	
4		Hickman, C	US 684483	2005	8	System for processing semiconductor	356/39			P	P	P		US 684483	
5		Mitaka, S	US 6790564	2004	14	Photomask and manufacturing metho	430/5	430/322		P	P	P		US 679056	
6		Okamoto, Y	US 6432790	2002	3	Method of manufacturing photomask	438/37	257/E21.57		P	P	P		US 643279	
7		Oshino, Tet	US 6208707	2001	11	X-ray projection exposure apparatus	378/34	378/84		P	P	P		US 620870	
8		Dirksen, Pe	US 5817604	1999	2	Alignment device and lithographic app	356/40	257/E23.17		P	P	P		US 581760	
9		Komoriya, A	US 543260	1995	5	Method of making semiconductor inte	356/40			P	P	P		US 54326	
10		Saitoh, Ken	US 5327221	1994	13	Device for detecting positional relatio	356/50			P	P	P		US 532722	

Ready

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